IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/666,025 Filing DateSeptember 17, 2003 Confirmation No.7937 Inventor Cem Basceri et al. AssigneeMicron Technology, Inc. ExaminerDavid P. Turocy Attorney's Docket No. MI22-3507 Title: Plasma Enhanced Chemical Vapor Deposition Method of Forming a Titanium Silicide Comprising Layer

RESPONSE TO OCTOBER 13, 2005 FINAL OFFICE ACTION PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING

To:

Mail Stop RCE

Commissioner for Patents

P. O. Box 1450

Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From:

Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)

Wells St. John P.S.

601 West First Avenue. Suite 1300

Spokane, WA 99201-3828

Responsive to the Final Office Action dated October 13, 2005, Applicant amends and remarks as follows:

10/31/2005 HLE333 00000143 10666025

AMENDMENTS

02 FC:1202

750.00 OP